

# Pavel Baroch

## List of Publications by Year in descending order

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25  
papers

818  
citations

840585

11  
h-index

677027

22  
g-index

25  
all docs

25  
docs citations

25  
times ranked

967  
citing authors

#	ARTICLE	IF	CITATIONS
1	Reactive magnetron sputtering of thin films: present status and trends. Thin Solid Films, 2005, 475, 208-218.	0.8	329
2	Bipolar pulsed electrical discharge for decomposition of organic compounds in water. Journal of Electrostatics, 2008, 66, 294-299.	1.0	76
3	Reactive magnetron sputtering of TiO <sub>x</sub> films. Surface and Coatings Technology, 2005, 193, 107-111.	2.2	69
4	Special type of plasma dielectric barrier discharge reactor for direct ozonization of water and degradation of organic pollution. Journal Physics D: Applied Physics, 2008, 41, 085207.	1.3	53
5	Discharge in dual magnetron sputtering system. IEEE Transactions on Plasma Science, 2005, 33, 338-339.	0.6	43
6	High sensitive detection of volatile organic compounds using superhydrophobic quartz crystal microbalance. Sensors and Actuators B: Chemical, 2012, 164, 15-21.	4.0	41
7	High-rate reactive deposition of transparent SiO <sub>2</sub> films containing low amount of Zr from molten magnetron target. Thin Solid Films, 2010, 519, 775-777.	0.8	32
8	High-rate pulsed reactive magnetron sputtering of oxide nanocomposite coatings. Vacuum, 2013, 87, 96-102.	1.6	26
9	Two-Functional Direct Current Sputtered Silver-Containing Titanium Dioxide Thin Films. Nanoscale Research Letters, 2009, 4, 313-320.	3.1	19
10	Hard Nanocomposite Coatings. , 2014, , 325-353.		19
11	Plasma Drift in Dual Magnetron Discharge. IEEE Transactions on Plasma Science, 2008, 36, 1412-1413.	0.6	15
12	Magnetron Discharges for Thin Films Plasma Processing. , 2006, , 67-110.		14
13	Enhancement of the deposition rate in reactive mid-frequency ac magnetron sputtering of hard and optically transparent ZrO <sub>2</sub> films. Surface and Coatings Technology, 2018, 336, 54-60.	2.2	12
14	Bipolar Pulsed Electrical Discharges in Liquid. IEEE Transactions on Plasma Science, 2008, 36, 1156-1157.	0.6	11
15	Generation of plasmas in water: utilization of a high-frequency, low-voltage bipolar pulse power supply with impedance control. Plasma Sources Science and Technology, 2011, 20, 034017.	1.3	10
16	Magnetron with gas injection through hollow cathodes machined in sputtered target. Surface and Coatings Technology, 2001, 148, 296-304.	2.2	8
17	In-Ga-Zn-O thin films with tunable optical and electrical properties prepared by high-power impulse magnetron sputtering. Thin Solid Films, 2018, 658, 27-32.	0.8	8
18	Elimination of Arcing in Reactive Sputtering of Al <sub>2</sub> O <sub>3</sub> Thin Films Prepared by DC Pulse Single Magnetron. Plasma Processes and Polymers, 2011, 8, 500-504.	1.6	7

#	ARTICLE	IF	CITATIONS
19	Rapid Sterilization of Escherichia coli by Solution Plasma Process. Japanese Journal of Applied Physics, 2012, 51, 126201.	0.8	7
20	Degradation of Bacteria Using Pulse Plasma Discharge in Liquid Medium. International Power Modulator Symposium and High-Voltage Workshop, 2006, , .	0.0	5
21	Atmospheric plasma-calcination of mesoporous tungsten oxide utilizing plasma dielectric barrier discharge. Thin Solid Films, 2007, 515, 4905-4908.	0.8	5
22	A study on the energy distribution for grid-assisting magnetron sputtering. Surface and Coatings Technology, 2005, 200, 421-424.	2.2	4
23	Tuning Stoichiometry and Structure of Pd-WO <sub>3</sub> ~x Thin Films for Hydrogen Gas Sensing by High-Power Impulse Magnetron Sputtering. Materials, 2020, 13, 5101.	1.3	3
24	Creating Biointerface on Polymer by Plasma-Initiated Graft Polymerization. Transactions of the Materials Research Society of Japan, 2011, 36, 549-552.	0.2	2
25	Tungsten Oxide Based Hydrogen Gas Sensor Prepared by Advanced Magnetron Sputtering. Engineering Proceedings, 2021, 6, .	0.4	0